

INFORMATION  
DISCLOSURE  
CITATION FORM FOR  
PATENT APPLICATION  
(FORM PTO - 1449)

Docket No.: 306 D12

Serial No.: 10/021,195

Applicant(s): KENNETH COLLINS, ET AL.

Filing Date: 10-30-01

Group: UNKNOWN

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FEB 20 2002  
TC 1700

## U. S. PATENTS

| Initials           | Patent No | Issue Date | Name              | Class | Subclass | Filing Date |
|--------------------|-----------|------------|-------------------|-------|----------|-------------|
| <i>[Signature]</i> | 4,123,316 | 10-31-78   | TSUCHIMOTO        |       |          |             |
| <i>[Signature]</i> | 4,261,762 | 04-14-81   | KING              |       |          |             |
| <i>[Signature]</i> | 4,350,578 | 09-21-82   | FRIESER ET AL.    |       |          |             |
| <i>[Signature]</i> | 4,368,092 | 01-11-83   | STEINBERG ET AL.  |       |          |             |
| <i>[Signature]</i> | 4,371,412 | 02-01-83   | NISHIZAWA         |       |          |             |
| <i>[Signature]</i> | 4,427,516 | 01-24-84   | LEVINSTEIN ET AL. |       |          |             |
| <i>[Signature]</i> | 4,427,762 | 01-24-84   | TAKAHASHI ET AL.  |       |          |             |
| <i>[Signature]</i> | 4,430,547 | 02-07-84   | YONEDA ET AL.     |       |          |             |
| <i>[Signature]</i> | 4,457,359 | 07-03-84   | HOLDEN            |       |          |             |
| <i>[Signature]</i> | 4,512,391 | 04-23-85   | HARRA             |       |          |             |

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| <i>[Signature]</i> | DE 39 42964 A1  | 27.06.91 | GERMANY | ROLAND GESCHE ET AL.   | N/A                          |
| <i>[Signature]</i> | EP 0 403 418 A2 | 19.12.90 | EUROPE  | GREGOR CAMPBELL ET AL. | N/A                          |
| <i>[Signature]</i> | EP 0 413 282 A2 | 20.02.91 | EUROPE  | JOHN OGLE              | N/A                          |
| <i>[Signature]</i> | EP 0 520 519 A1 | 30.12.92 | EUROPE  | JEFFREY MARKS ET AL.   | N/A                          |
| <i>[Signature]</i> | EP 0 552 490 A1 | 28.07.93 | EUROPE  | JEFFREY MARKS ET AL.   | N/A                          |
| <i>[Signature]</i> | EP 0 552 491 A1 | 28.07.93 | EUROPE  | KENNETH COLLINS ET AL. | N/A                          |

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| <i>[Signature]</i> | Coburn, W.J., "Increasing the Etch Rate Ratio $\text{oSiO}_2/\text{Si}$ in Fluorocarbon Plasma Etching," <i>IBM Technical Disclosure</i> , Vol. 19, No. 10, March 1997.  |
| <i>[Signature]</i> | Cook, J.M., Ibbatson, D.E., and Flamm, D.L., "Application of a low-pressure radio frequency discharge source to polysilicon gate etching," <i>J. Vac. Sci. Technol.</i> , Vol. B8, No. 1, Jan/Feb 1990, pp. 1-5. |

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Date Considered: 1/21/03

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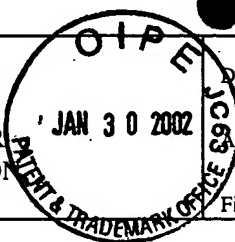
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| AKM      | 4,565,601 | 01-21-86   | KAKEHI ET AL.      |       |          |             |
|          | 4,572,759 | 02-29-86   | BENZING            |       |          |             |
|          | 4,579,080 | 04-01-86   | MARTIN ET AL.      |       |          |             |
|          | 4,711,698 | 12-08-87   | DOUGLAS            |       |          |             |
|          | 4,755,345 | 07-05-88   | BAITY, JR. ET AL.  |       |          |             |
|          | 4,756,810 | 07-12-88   | LAMONT, JR. ET AL. |       |          |             |
|          | 4,786,352 | 11-22-88   | BENZING            |       |          |             |
|          | 4,786,359 | 11-22-88   | STARK ET AL.       |       |          |             |
|          | 4,793,897 | 12-27-88   | DUNFIELD ET AL.    |       |          |             |
|          | 4,793,945 | 12-27-88   | SIREN              |       |          |             |

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| AKM      | EP 0 596 551 A1 | 11.05.94 | EUROPE  | JEFFREY BENZING ET AL. | N/A                          |
|          | EP 0 601 468 A1 | 15.06.94 | EUROPE  | KENNETH COLLINS ET AL. | N/A                          |
|          | EP 0 641 013 A2 | 01.03.95 | EUROPE  | KEVIN FAIRBAIRN ET AL. | N/A                          |
|          | EP 0 651 434 A2 | 03.05.95 | EUROPE  | NICOLAS BRIGHT ET AL.  | N/A                          |
|          | EP 0 680 072 A2 | 02.11.95 | EUROPE  | FRED REDECKER ET AL.   | N/A                          |
|          | EP 0 702 391 A2 | 20.03.95 | EUROPE  | DIANA MA ET AL.        | N/A                          |

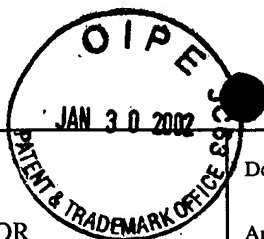
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| AKM      | Horiike, Y., Kubota, K., Shindo, H., and Fukasawa, T., "High rate and highly selective SiO <sub>2</sub> etching employing inductively coupled plasma and discussion on reaction kinetics," <i>J. Vac. Sci. Technol.</i> , Vol. 13, No.3, May/June 1995, pp.801-809 |
| AKM      | Lee, H., Dong-II, Y., and Whang, J., "The effects of magnetic fields on a planar inductively coupled argon plasma," <i>Plasma Sources Sci. Technol.</i> , 5(1996), pp. 383-388.  |

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|          | 4,807,016 | 02-21-89   | DOUGLAS         |       |          |             |
|          | 4,810,935 | 03-07-89   | BOSWELL         |       |          |             |
|          | 4,828,369 | 05-09-89   | HOTOMI          |       |          |             |
|          | 4,842,683 | 06-27-89   | CHENG ET AL.    |       |          |             |
|          | 4,844,775 | 07-04-89   | KEEBLE          |       |          |             |
|          | 4,849,675 | 07-18-89   | MULLER          |       |          |             |
|          | 4,859,908 | 08-22-89   | YOSHIDA ET AL.  |       |          |             |
|          | 4,870,245 | 09-26-89   | PRICE ET AL.    |       |          |             |
|          | 4,918,031 | 04-17-90   | FLAMM ET AL.    |       |          |             |
| ↓        | 4,948,458 | 08-14-90   | OGLE            |       |          |             |

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| DKM      | EP 0 710 055 A1 | 01.05.96 | EUROPE  | XUE-YU QIAN ET AL.      | N/A                          |
|          | EP 0 727 807 A1 | 21.08.96 | EUROPE  | HIROJI HANAWA           | N/A                          |
|          | EP 0 727 923 A1 | 12.08.96 | EUROPE  | HIROJI HANAWA           | N/A                          |
|          | EP 0 742 577 A2 | 31.11.96 | EUROPE  | YAN YE ET AL.           | N/A                          |
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| ↓        | Matsuo, Seitaro, "Selective Etching of siO <sub>2</sub> Relative to Si by Plasma Reactive Sputter Etching," <i>J. Vac. Sc. Technology</i> , Vol. 17, No. 2, March-April 1980. |

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|          | 4,990,229 | 02-05-91   | CAMPBELL ET AL. |       |          |             |
|          | 5,000,113 | 03-19-91   | WANG ET AL.     |       |          |             |
|          | 5,006,220 | 04-09-91   | HIJIKATA ET AL. |       |          |             |
|          | 5,015,330 | 05-14-91   | OKUMURA ET AL.  |       |          |             |
|          | 5,032,202 | 06-16-91   | TSAI ET AL.     |       |          |             |
|          | 5,074,456 | 12-24-91   | DEGNER ET AL.   |       |          |             |
|          | 5,085,727 | 02-04-92   | STEGE           |       |          |             |
|          | 5,122,251 | 06-16-92   | CAMPBELL ET AL. |       |          |             |
|          | 5,169,487 | 12-08-92   | LANGLEY ET AL.  |       |          |             |
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| RCM      | GB 231,197      | 07.11.90 | GREAT BRITAIN | MERVYN DAVIS ET AL.      | N/A                          |
|          | JP 55-9464      | 23.01.80 | JAPAN         | OSAMU OZAWA              | YES                          |
|          | JP 55-154582    | 02.12.80 | JAPAN         | TOYOTA HIROYASU ET AL.   | N/A                          |
|          | JP 57-155732    | 25.09.82 | JAPAN         | RIYOUHEI KAWABATA        | YES                          |
|          | JP 61-147531    | 21.12.84 | JAPAN         | OTANI YASIKAZU           | N/A                          |
|          | JP 61-91377     | 09.05.86 | JAPAN         | ATSUSHI SEKIGUCHI ET AL. | N/A                          |

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| RCM      | Samukawa, S., and Ohtake, H., "Pulse-time Modulated Plasma Etching for Precise ULSI Patterning," Abstract No. 162, <i>Microelectronics Research Laboratories</i> , NEC Corporation, Japan, May 1996, pp. 217-218.                     |

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|          | 5,210,466 | 05-11-93   | COLLINS ET AL.  |       |          |             |
|          | 5,226,154 | 07-06-93   | KONDOH          |       |          |             |
|          | 5,241,245 | 08-31-93   | BARNES ET AL.   |       |          |             |
|          | 5,249,251 | 09-28-93   | EGALON ET AL.   |       |          |             |
|          | 5,258,824 | 11-02-93   | CARLSON ET AL.  |       |          |             |
|          | 5,271,788 | 12-21-93   | HASEGAWA ET AL. |       |          |             |
|          | 5,275,683 | 01-04-94   | ARAMI ET AL.    |       |          |             |
|          | 5,276,693 | 01-04-94   | LONG ET AL.     |       |          |             |
|          | 5,277,751 | 01-11-94   | OGLE            |       |          |             |
|          | 5,326,404 | 07-05-94   | SATO            |       |          |             |

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| RCM      | JP 61-142744    | 30.06.86 | JAPAN   | SHINGO KADOMURA           | YES                          |
|          | JP 62-7268      | 14.01.87 | JAPAN   | SETSUHIKO UEDA            | YES                          |
|          | JP 62-12129     | 21.01.87 | JAPAN   | MASAYOSHI SERIZAWA ET AL. | YES                          |
|          | JP 62-249422    | 30.10.87 | JAPAN   | KOICHIRO KAWAMURA ET AL.  | YES                          |
|          | JP 62-254428    | 06.11.87 | JAPAN   | AZIRA OZAWA ET AL.        | YES                          |
|          | JP 63-9120      | 14.01.88 | JAPAN   | YOSHISANE OKAMURA         | N/A                          |

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| RCM      | Shibano, T., Fujiwara, N., Hirayama, M., Nagata, H., and Demizu, K., "Etching of SiO <sub>2</sub> by low energy CF+x and F <sup>+</sup> ions," <i>Appl. Phys. Lett.</i> , Vol. 63, No. 17, October 25, 1993, pp. 2336-2338. |
| RCM      | Suagi, H., and Nakamura, K., "Diagnostics and control of radicals in an inductively coupled etching reactor," <i>J. Vac. Sci. Technol.</i> , Vol. 13, No. 3, May/June 1995, pp. 8878-893.                                   |

Examiner's Signature: *Richard*

Date Considered: 01/21/03

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|          | 5,399,237 | 03-21-95   | KESWICK ET AL.  |       |          |             |
|          | 5,401,350 | 03-28-96   | PATRICK ET AL.  |       |          |             |
|          | 5,414,246 | 05-09-95   | SHAPONA         |       |          |             |
|          | 5,421,891 | 06-06-95   | CAMPBELL ET AL. |       |          |             |
|          | 5,423,945 | 06-13-95   | MARKS ET AL.    |       |          |             |
|          | 5,449,432 | 09-12-95   | HANAWA          |       |          |             |
| ✓        | 5,468,341 | 11-21-95   | SAMUKAWA        |       |          |             |

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| SLW      | JP 63-155728    | 28.06.88 | JAPAN   | YASUhide SATO              | YES                          |
|          | JP 64-15928     | 19.01.89 | JAPAN   | YOSHITSUGI FUKUYAMA ET AL. | YES                          |
|          | JP 4-94121      | 26.03.92 | JAPAN   | KAZUhide ONO               | YES                          |
|          | WO 91/10341     | 11.07.91 | PCT     | STEPHEN SAVAS ET AL.       | N/A                          |
|          | WO 92/20833     | 26.11.92 | PCT     | MARK WEISE ET AL.          | N/A                          |
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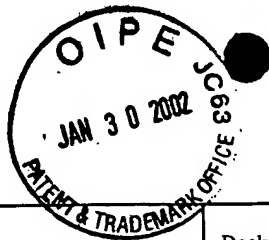
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Examiner's Signature: *Alejandro*

Date Considered: 01/21/03

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|            | 5,529,657 | 06-25-96   | ISHII          |       |          |             |
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|            | 5,607,542 | 03-04-97   | WU ET AL.      |       |          |             |
|            | 5,683,538 | 11-04-97   | O'NEILL ET AL. |       |          |             |
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Examiner's Signature: *Delegando*

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|                    | 6,095,083 | 08-01-00   | RICE ET AL.    |       |          |             |
|                    | 6,095,084 | 08-01-00   | SHAMOULIAN     |       |          |             |
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| Initials | Document Number  | Date | Country | Name | Translation?<br>(Yes/No/n/a) |
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